



## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Fukuda et al. ) Group Art Unit 1763  
Appl. No. : 09/511,934 )  
Filed : February 24, 2000 )  
For : THIN-FILM FORMING )  
APPARATUS HAVING AN )  
AUTOMATIC CLEANING )  
FUNCTION FOR CLEANING )  
THE INSIDE )  
Examiner : R. Kackar )

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AMENDMENT

Assistant Commissioner for Patents  
Washington, D.C. 20231

Dear Sir:

In response to the Office Action mailed November 20, 2002 (Paper number 13), please amend the above-identified application as follows:

IN THE CLAIMS:

**Please cancel Claim 8.**

**Please amend Claim 1 as follows:**

1. (Fifth amended) A thin film forming apparatus comprising:
- a reaction chamber for forming a film formation temperature of 500°C or higher a thin film on a workpiece placed on a susceptor and below a showerhead provided in the reaction chamber, said susceptor being made of aluminum nitride and provided with a heater for heating the workpiece, said reaction chamber being provided with a conveyer for loading and unloading the workpiece into and from the reaction chamber; and
- a cleaning device for cleaning unwanted deposits adhering to the inside of the reaction chamber at predetermined intervals, said cleaning device comprising: